

	L #	Hits	Search Text
1	L1	478	((wafer or substrate) near3 stage) with (reference near3 (mark or position))
2	L2	549	((wafer or substrate) near3 (table or stage)) with (reference near3 (mark or position))
3	L3	14561	(detect\$3 or sens\$3 or locat\$3) near5 (reference near3 (mark or position))
4	L4	358	2 and 3
5	L5	236	4 and (355/\$.ccls. or 356/399-401.ccls. or 250/548.ccls.)
6	L6	163	@ad<=20000907 and 5
7	L7	97	(calibrat\$3 or correlat\$3 or scal\$3) and 6
8	L8	5	((("6208407") or ("5669441") or ("5835275") or ("5717518") or ("5715064")).PN.
9	L9	5	((("6208407") or ("5969441") or ("5835275") or ("5717518") or ("5715064")).PN.
10	L10	5	((("5689337") or ("5684856") or ("5668672") or ("5488229") or ("5473410")).PN.
11	L11	18900	tanaka.in.
12	L12	4587	11 and stage

	L #	Hits	Search Text
13	L13	664	12 and (mask or reticle) and (substrate or wafer)
14	L14	1484	11 and (mask or reticle) and (substrate or wafer)
15	L15	288	12 and (stage or table) and (reference near3 (mark or position))
16	L16	46	15 and interferometer
17	L17	31	16 and nikon.as.
18	L18	10	5715064.uref.
19	L19	12550	((substrate or wafer) near2 stage)
20	L20	685	((substrate or wafer) near2 stage near5 (first and second))
21	L21	1489	((substrate or wafer) near2 stage near5 first)
22	L22	1065	((substrate or wafer) near2 stage near5 second)
23	L23	685	21 and 22
24	L24	236	((measur\$5 or characterization) near2 station) and ((project\$3 or imag\$3) near2 station)

	L #	Hits	Search Text
25	L25	917	23 or 24
26	L26	127055	(mask or reticle) and (substrate or wafer)
27	L27	428	25 and 26
28	L28	253	@ad<=20000907 and 27
29	L29	151	28 and (355/\$.ccls. or 356/399-401.ccls. or 250/548.ccls.)
30	L30	155	28 and (310/\$.ccls. or 355/\$.ccls. or 356/399-401.ccls. or 250/548.ccls.)
31	L31	110	30 and interferometer
32	L32	17431	(detect\$3 or sens\$3 or locat\$3 or measur\$5) near5 (reference near3 (mark or position))
33	L33	54	31 and 32

PK  
10/25/03